

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Ritzdorf et al. )  
 )  
 For: Method and Apparatus for )  
 Low-Temperature Annealing of )  
 Metallization Microstructures in )  
 the Production of a )  
 Microelectronic Device )  
 )  
 Serial No.: )  
 )  
 Filed: August 31, 1999 )  
 )  
 Examiner: )  
 )  
 Art Unit: )

*JA*  
*D.G.*  
*1-18-00*

**PRELIMINARY AMENDMENT**

Box Patent Application  
 Assistant Commissioner for Patents  
 Washington, D.C. 20231

Dear Sir:

Please preliminarily amend the application filed herewith, as follows:

**IN THE SPECIFICATION:**

Please amend the specification as follows:

On page 1, line 9, amend "Not Applicable" after "CROSS-REFERENCE TO

RELATED APPLICATIONS" to --This is a continuation application of International PCT Patent Application No. PCT/US99/02504, designating the US, filed February 4, 1999, entitled METHOD AND APPARATUS FOR LOW TEMPERATURE ANNEALING OF METALLIZATION MICRO-STRUCTURES IN THE PRODUCTION OF A MICROELECTRONIC DEVICE, which claims priority from US Patent Application Serial No.

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